

33082R003



PATENT
EXPEDITED PROCESSING
AFTER FINAL STATUS

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07/28/00

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants : NANBU, et al.

Serial No. : 09/233,073

Examiner: Vinh, L.

Filed : January 19, 1999

Group Art Unit: 1765

For : METHOD OF ETCHING

PETITION UNDER 37 C.F.R. §1.97(d)

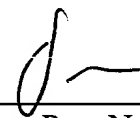
Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

In accordance with 37 C.F.R. §1.97(d), Applicants respectfully request entry and consideration of the attached Information Disclosure Statement. Applicants attach a Certification Under 37 C.F.R. §1.97(e)(2) hereto. Also attached hereto is a check in the amount of \$130 for the associated Petition fee. Please charge any additional fees or credit any overpayment to Deposit Account No. 02-4300.

Respectfully submitted,

SMITH, GAMBRELL & RUSSELL, LLP
The Beveridge, Degrandi, Weilacher & Young
Intellectual Property Group

By: 
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July 26, 2000

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CERTIFICATION UNDER 37 C.F.R. § 1.97(e)(2)

In accordance with 37 C.F.R. § 1.97(e)(2), Applicants certify that no item of information contained in the accompanying information disclosure statement was cited in a communication from a foreign patent office in counterpart foreign application, and to the knowledge of the person signing the statement after making reasonable inquiry, no item of information contained in the information disclosure statement was known to any individual designated in § 1.56(c) more than three months prior to the filing of the information disclosure statement.

Respectfully submitted,

SMITH, GAMBRELL & RUSSELL, LLP
BEVERIDGE, DEGRANDI, WEILACHER & YOUNG
INTELLECTUAL PROPERTY GROUP

By: 

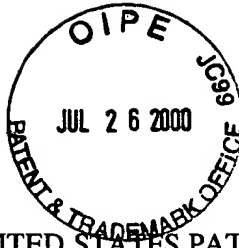
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July 26, 2000

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EXPEDITED PROCESSING
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INFORMATION DISCLOSURE STATEMENT
WITH PETITION UNDER 37 C.F.R. 1.97(d)

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

This Information Disclosure Statement is further to the Amendment After Final filed on July 24, 2000 for the above-identified case and is accompanied by the following documents:

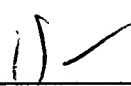
- 1) PTO 1449 form citing two references
- 2) Petition Under 37 C.F.R. 1.97(d)
- 3) Certification Under 37 C.F.R. 1.97(e)(2)
- 4) Copy of each article referenced in (1) above
- 5) Check for \$130.00

Entry and consideration of the references accompanying this Information Disclosure Statement (and also earlier provided with the Amendment After Final) is respectfully requested.

Respectfully submitted,

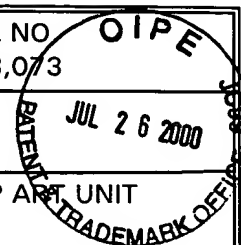
SMITH, GAMBRELL & RUSSELL, LLP
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JUL 27 2000
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FORM PTO-1449 INFORMATION DISCLOSURE STATEMENT <i>(Use several sheets if necessary)</i>	ATTY. DOCKET NO. 33082R003	SERIAL NO 09/233,073
	APPLICANT: NANBU, et al.	
	FILING DATE January 19, 1999	GROUP AND UNIT 1765



U.S. Patent Documents

Examiner Initials		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB-CLASS	FILING DATE, IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						

Foreign Patent Documents

Examiner Initials		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS	TRANSLATION	
							YES	NO
	AH							
	AI							
	AJ							
	AK							
	AL							
	AM							
	AN							
	AO							
	AP							

OTHER INFORMATION (Including Author, Title, Date, Pertinent Pages, Etc.)

LV	AQ	Two-Dimensional Modeling of High Plasma Density Inductively Coupled Sources for Materials Processing, J. Vac Sci. Technol. B 12(1), Jan/Feb 1994, pp. 461-476
LV	AR	"Hybrid Plasma Equipment Model Inductively Coupled Plasma Reactive Ion Etching Reactors" Computational Optical and Discharge Physics, University of Illinois College of Engineering, pp. 1-4 (date not designated)
	AS	
	AT	
	AU	

EXAMINER LAN VINH	DATE CONSIDERED 7/28/2000
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